

# [WATER CLEANING APPARATUS]

## Abstract

A wafer cleaning apparatus is provided. The wafer cleaning apparatus comprises a trough, a wafer holder, a rolling device, and a fluid injecting device. The wafer holder is disposed in the trough for holding a plurality of wafers. The rolling device is disposed in the trough and contacts with the wafers held on the wafer holder for rotating the wafers. The fluid injecting device is disposed in the trough for supplying cleaning liquid for cleaning the wafers.